

Please type a plus sign (+) inside this box → [+]

PTO/SB/08A (08-00)

Approved for use through 10/31/2002. OMB 0651-0031

Approved for use through 10/31/2002. GPO: 0-091-0051  
U.S. Patent and Trademark Office: U.S. DEPARTMENT OF COMMERCE

U.S. Patent and Trademark Office, U.S. DEPARTMENT OF COMMERCE

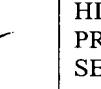
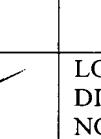
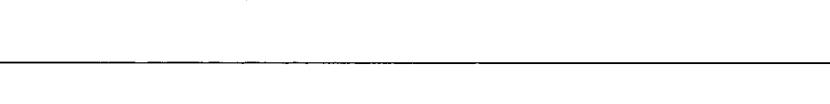
<p><b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b></p> <p><i>(use as many sheets as necessary)</i></p>				<b>Complete if Known</b>	
				<b>Application Number</b>	09/732,927
				<b>Filing Date</b>	December 11, 2000
				<b>First Named Inventor</b>	Nobuo SHIMAZU et al.
				<b>Group Art Unit</b>	Unknown
				<b>Examiner Name</b>	Unknown
<b>Sheet</b>	1	of	1	<b>Attorney Docket Number</b>	740107-135

## **U.S. PATENT DOCUMENTS**

## **FOREIGN PATENT DOCUMENTS**

FOREIGN PATENT DOCUMENTS						
Examiner Initials <sup>1</sup>	Cite No. <sup>1</sup>	Foreign Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Office <sup>3</sup>	Number <sup>4</sup> <i>(if known)</i>			

#### **OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS**

Examiner Initials*	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>
		HIGH THROUGHPUT SUBMICRON LITHOGRAPHY WITH ELECTRON BEAM PROXIMITY PRIMING, H. BOHLEN ET AL., SOLID STATE TECHNOLOGY, SEPTEMBER 1984, PAGES 210-217	
		LOW ENERGY ELECTRON-BEAM PROXIMITY PROJECTION LITHOGRAPHY: DISCOVERY OF MISSING LINK, TAKAO UTSUMI, J. VAC. SCI. TECHNOL. B 17(6), NOVEMBER/DECEMBER 1999, PAGES 2897-2902	
			

Examiner Signature  Date Considered 6-30-02

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<sup>1</sup> Unique citation designation number. <sup>2</sup> See attached Kinds of U.S. Patent Documents. <sup>3</sup> Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). <sup>4</sup> For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. <sup>5</sup> Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.16 if possible. <sup>6</sup> Applicant is to place a check mark here if English language Translation is attached.

<sup>1</sup> Unique citation designation number. <sup>2</sup> Applicant is to place a check mark here if English language Translation is attached.